



B

PATENT  
30205/37328

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application of:	)	I hereby certify that this paper is
	)	being deposited with the United
<b>JUNG et al.</b>	)	States Postal Service as first class
	)	mail, postage prepaid, in an
Serial No.: 09/878,803	)	envelope addressed to
	)	Commissioner for Patents, P.O.
Filed: June 11, 2001	)	Box 1450, Alexandria, Virginia
	)	22313-1450 on this date:
For: ADDITIVE FOR	)	<b>April 8, 2004</b>
PHOTORESIST COMPOSITION	)	
FOR RESIST FLOW PROCESS	)	
	)	
Group Art Unit: 1752	)	Michael R. Hull
	)	Registration No. 35,902
Examiner: Yvette C. Thornton	)	Attorney for Applicants

## COMMENT ON STATEMENT OF REASONS FOR ALLOWANCE

Commissioner for Patents  
P.O. Box 1450  
Alexandria, Virginia 22313-1450

Sir:

In addition to the reasons for allowance set forth in the allowance papers that were mailed in connection with the present application, it is respectfully submitted that the claims are allowable for the additional reasons that the invention defined by the language of the claims is neither anticipated by, nor would have been obvious when taken as a whole in view of, the art of record.

Respectfully submitted,

MARSHALL, GERSTEIN & BORUN LLP  
6300 Sears Tower  
233 South Wacker Drive  
Chicago, Illinois 60606-6357  
(312) 474-9577

By: 

Michael R. Hull  
Registration No. 35,902  
Attorney for Applicants

April 8, 2004

734681